

3D Stacked Buck Converter with SrTiO₃ (STO) Capacitors on Silicon Interposer

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Outline

Introduction

- Fine-grained voltage engineering
- 3D stacked DC-DC (buck) converter

Silicon Interposer

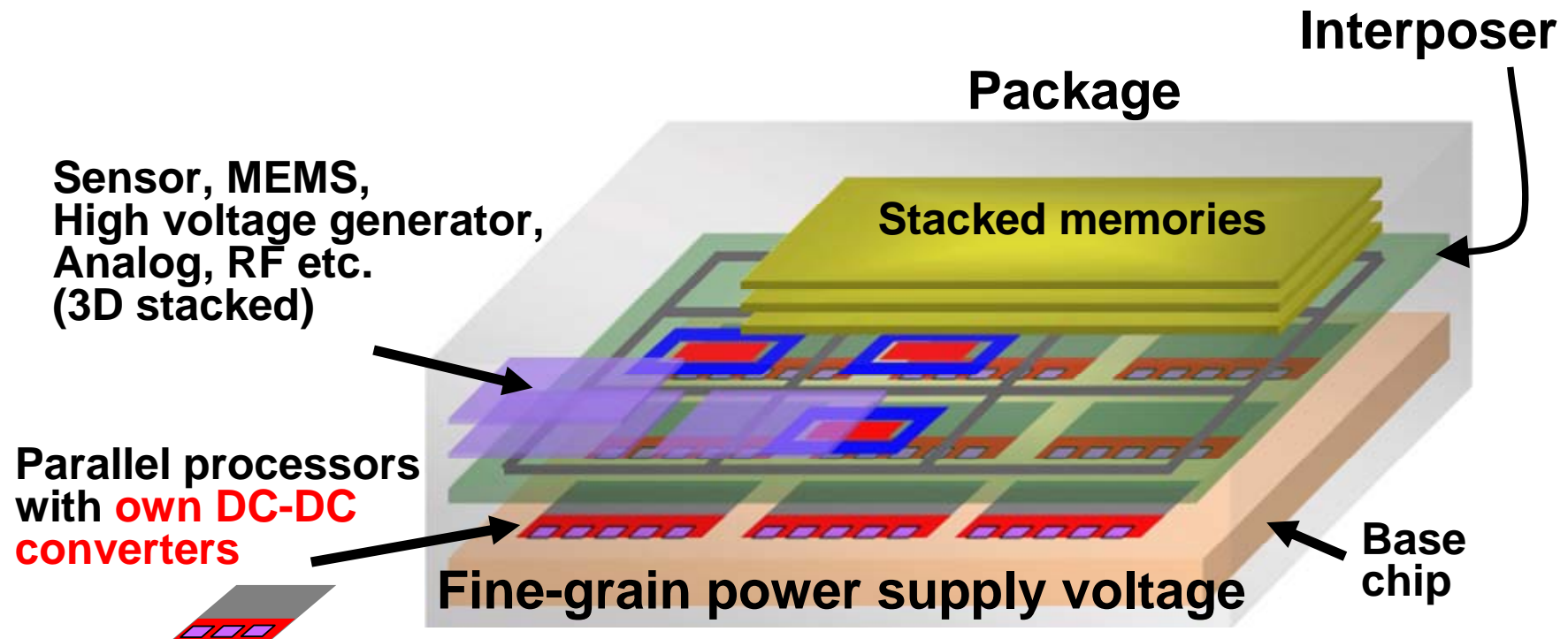
- $1.5\mu\text{F}/\text{cm}^2$ SrTiO₃ (STO) capacitor
- 15 μm thick inductor

Measured Efficiency of Buck Converter

Summary

Power Supply for High-Performance 3D-LSIs

- Heterogeneous integration \Rightarrow Various power supplies
- Low-power and high-performance
 \Rightarrow Fine-grained voltage engineering

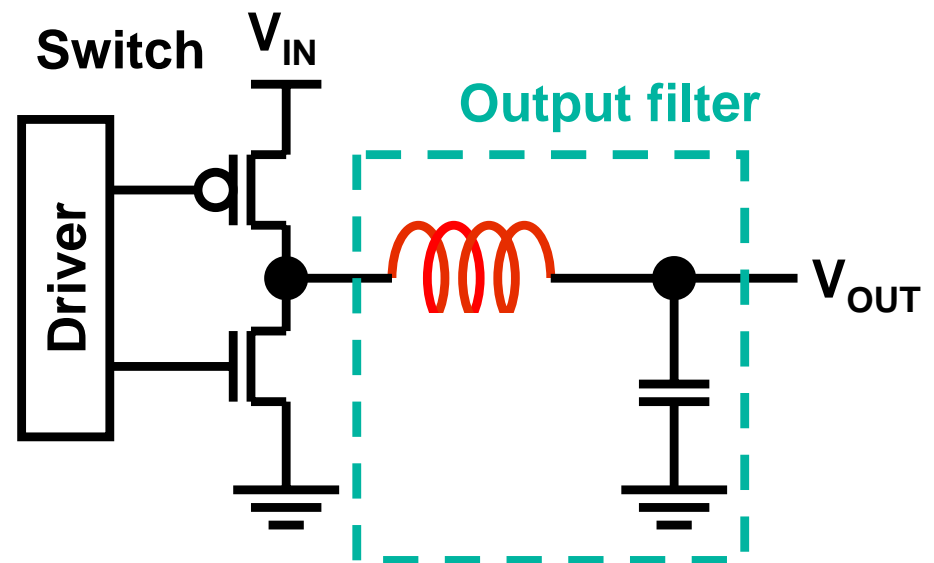


On-chip DC-DC (buck) converters are essential for 3D LSIs.

On-Chip Buck Converters

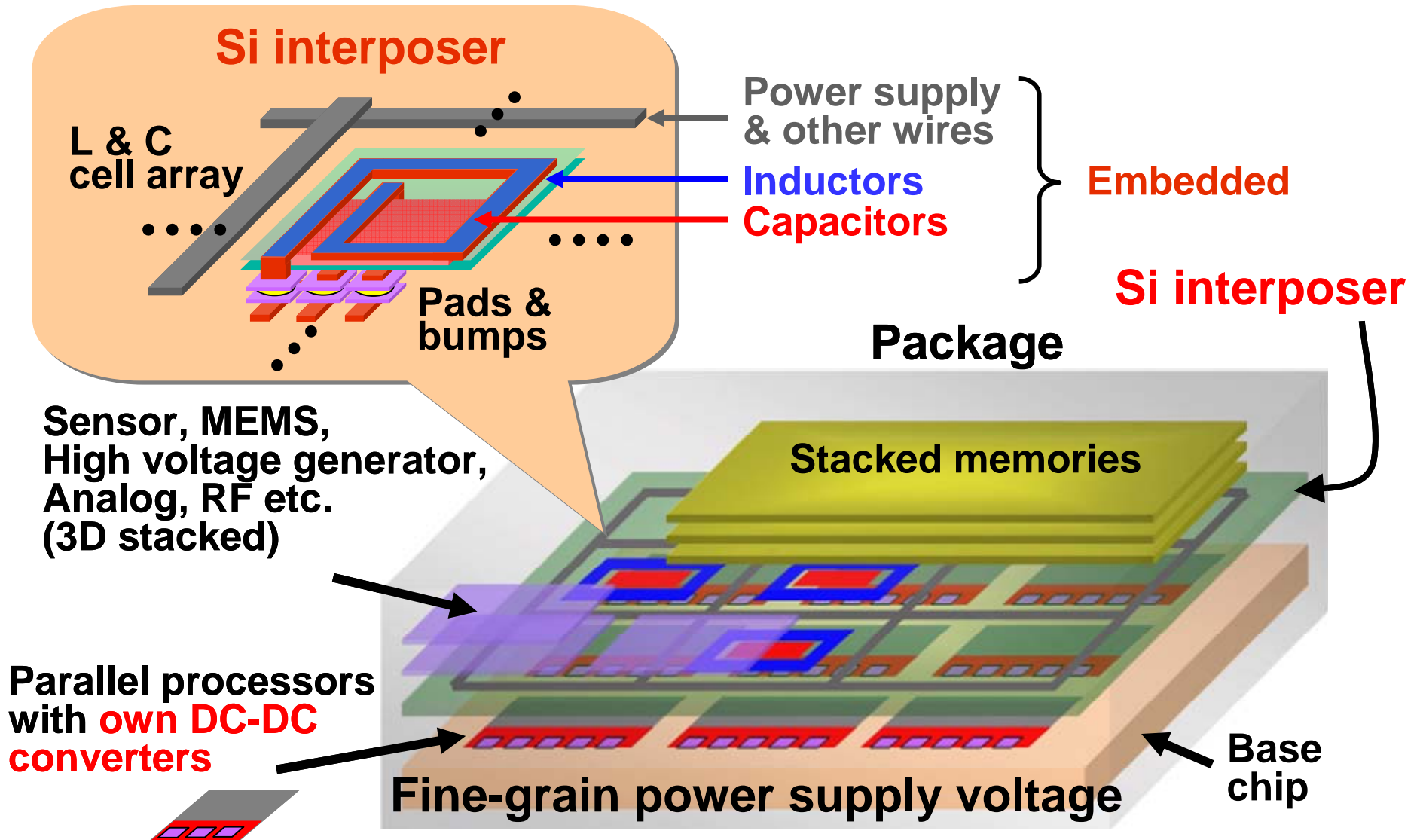
Disadvantages of on-chip inductors

- Smaller inductance < 10 nH
- Area penalty
- Parasitic resistance due to thin conductors



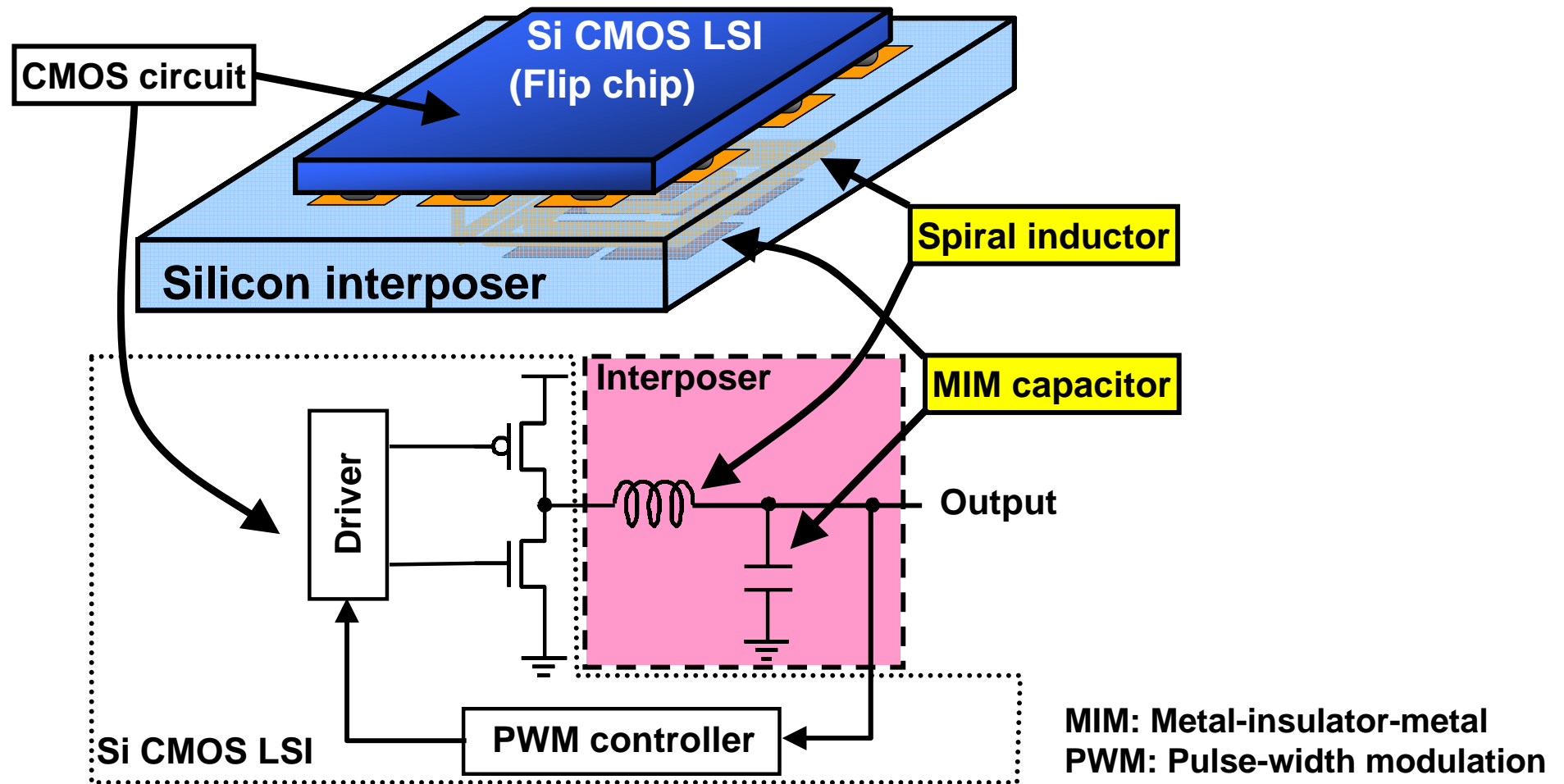
Inductors should be thick and separated from a Si chip.

Concept of 3D Stacked Distributed Power Supply



Output LC filters is embedded into a Si interposer.

Proposed 3D Stacked Buck Converter



Area penalty and parasitic resistance will be small.

K. Takemura, K. Ishida, Y. Ishii, K. Maeda, M. Takamiya, T. Sakurai, and K. Baba, "Si Interposers with Thick Spiral Inductors for 3D Stacked Buck Converters," ICEP, TA4-1, Apr. 2011.

K. Ishida, K. Takemura, K. Baba, M. Takamiya, and T. Sakurai, "3D Stacked Buck Converter with 15um Thick Spiral Inductor on Silicon Interposer for Fine-Grain Power-Supply Voltage Control in SiP's," IEEE International 3D System Integration Conference, pp. 1-4, Nov. 2010.

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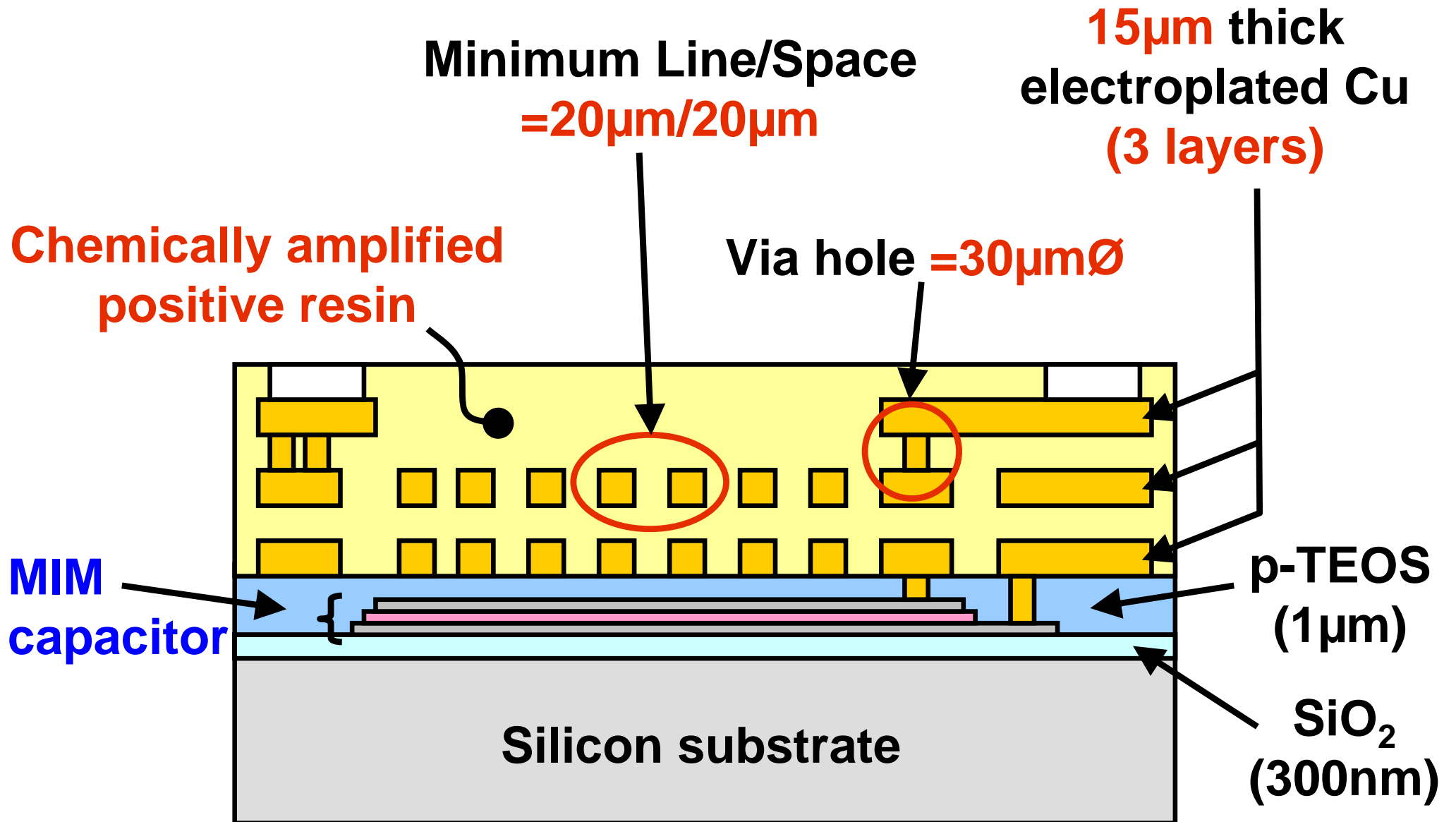
Silicon Interposer

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Fabrication Process of Silicon Interposer

MIM cap. fabrication



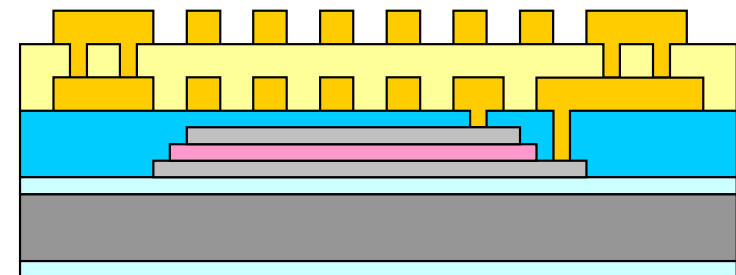
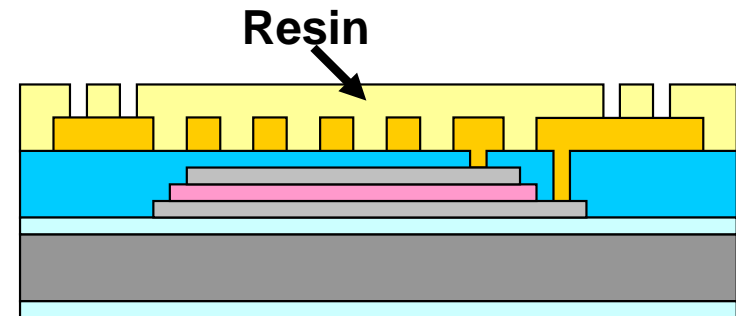
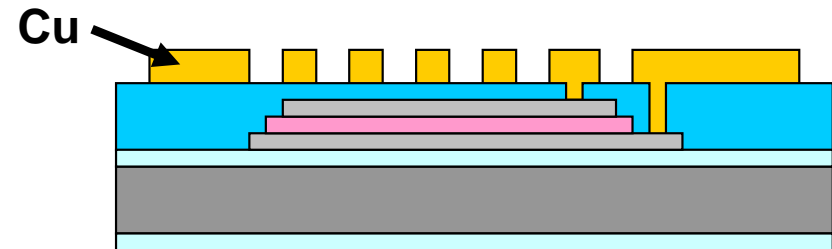
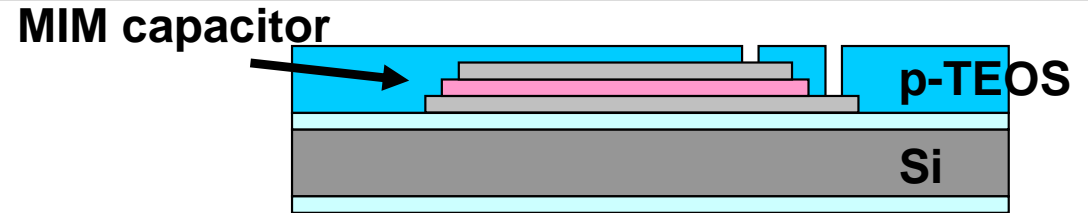
Cu electroplating



ILD resin formation



Repetition



ILD: Interlayer dielectric

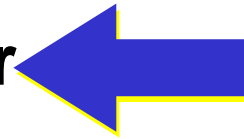
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- **1.5 μ F/cm² SrTiO₃ (STO) capacitor**
- 15 μ m thick inductor

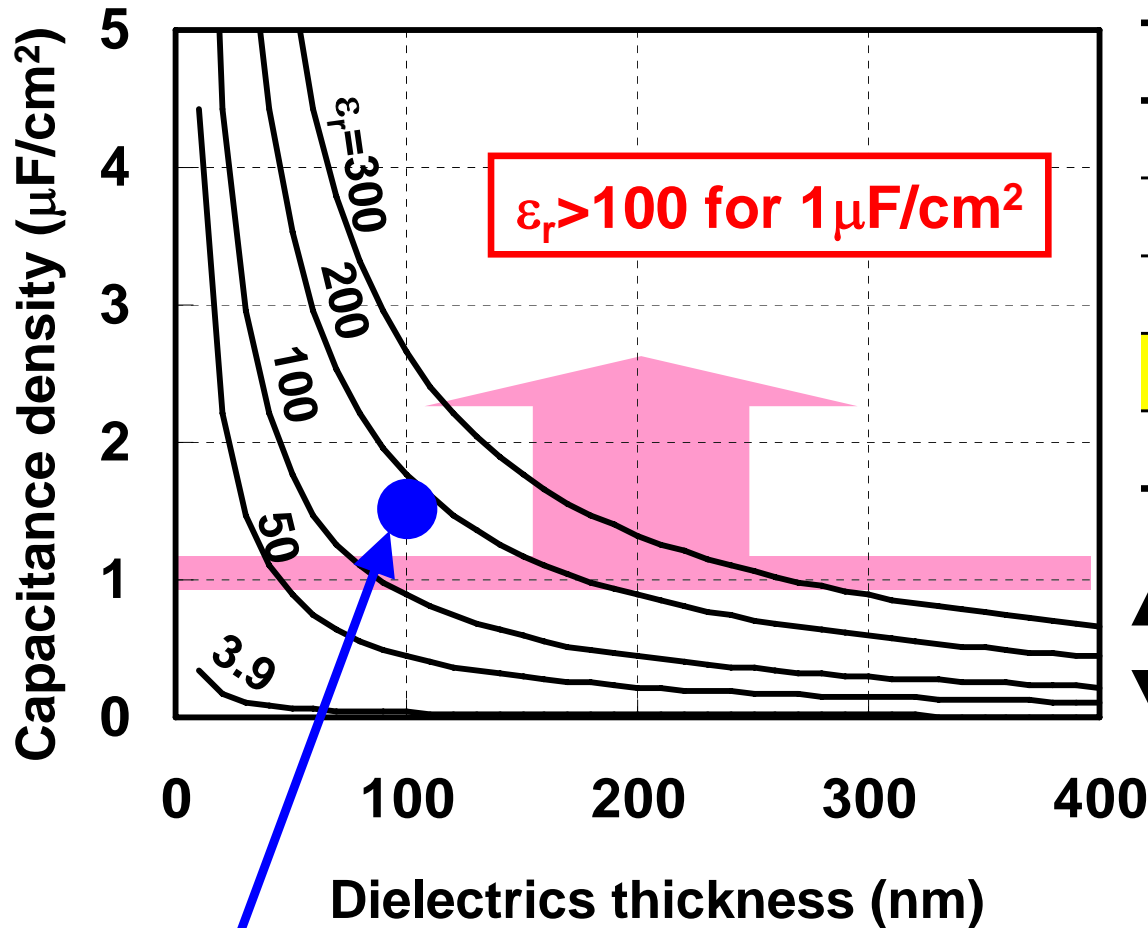


Measured Efficiency of Buck Converter

Summary

Capacitor Dielectrics

When the target capacitance density is higher than $1\mu\text{F}/\text{cm}^2$, ferroelectric and related oxides are preferable.



| Dielectrics | ϵ_r |
|--|------------------|
| SiO_2 | 3.9 |
| Si_3N_4 | 7 ~ 9 |
| Ta_2O_5 | 20 ~ 50 |
| SrTiO_3 (thin film) | 100 ~ 600 |
| $\text{Pb}(\text{Zr},\text{Ti})\text{O}_3$ (thin film) | 500 ~ 1000 |

On-chip planar capacitors

This work (100nm, $1.5\mu\text{F}/\text{cm}^2$, $\epsilon_r > 100$)

SrTiO₃ Thin Film Capacitor Fabrication

➤ Advantages

Low crystallization temperature

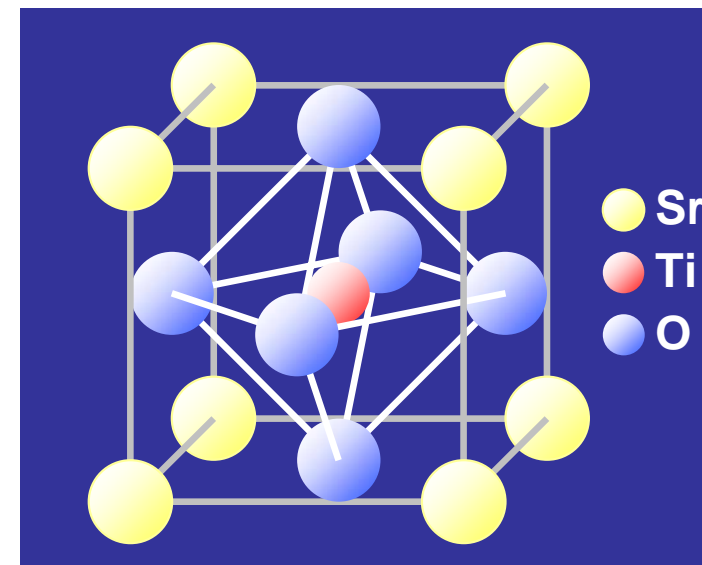
Ease of composition control

➤ Examples of STO capacitor applications

DRAM cell capacitor (on-chip)

GaAs MMIC (on-chip)

Polyimide-based flexible capacitor (discrete)

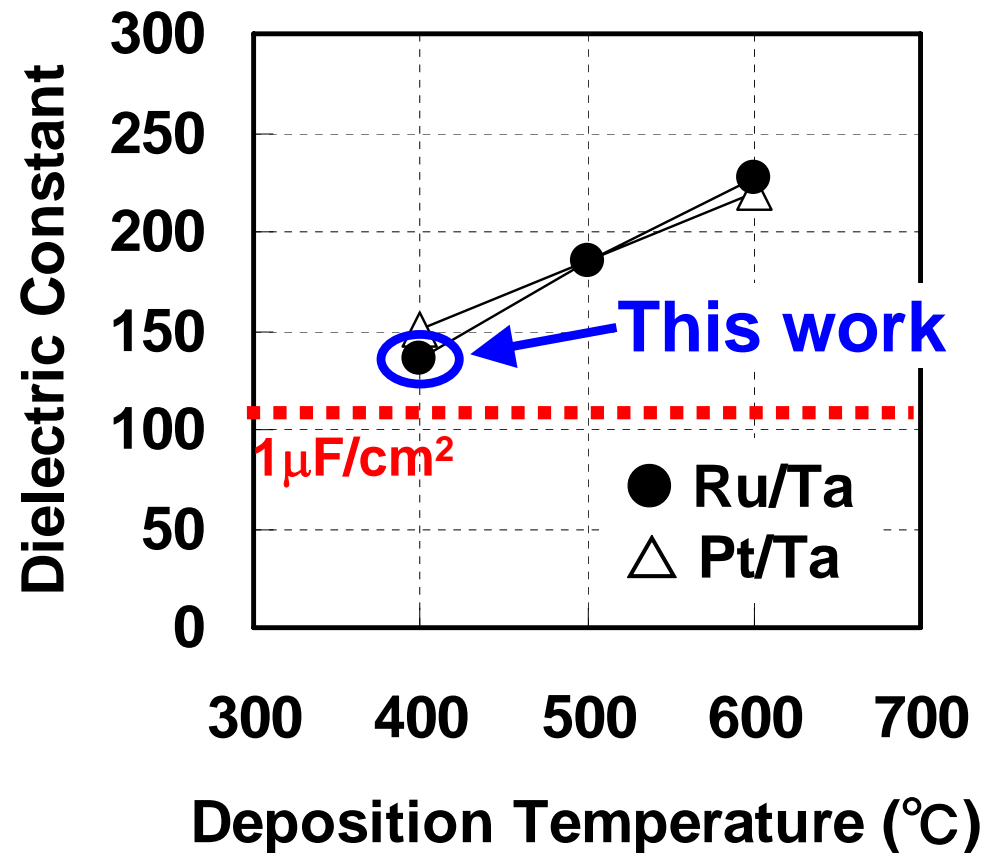


Reactive sputtering conditions

| | |
|------------------|-----------------------------|
| Target | SrTiO ₃ ceramics |
| Sputtering Gas | 80% Ar - 20% O ₂ |
| Deposition Temp. | 400°C |
| Bottom Electrode | Ru/Ta |
| Top Electrode | Ru |

Properties for Sputtered STO Thin Films

Higher ϵ_r than 100, and good insulating properties



Capacitor size: 100μm x 100μm
STO thickness: 100nm

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- **15 μm thick inductor** 

Measured Efficiency of Buck Converter

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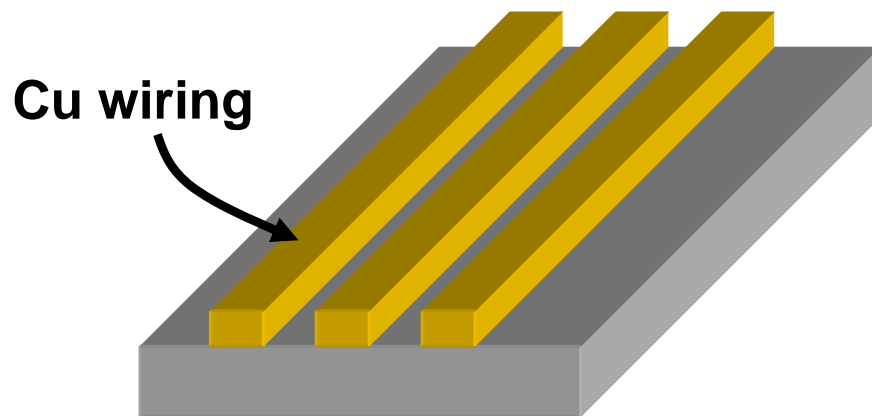
Process Issues for 15- μm -Thick Cu Wiring

Fine Cu pattering

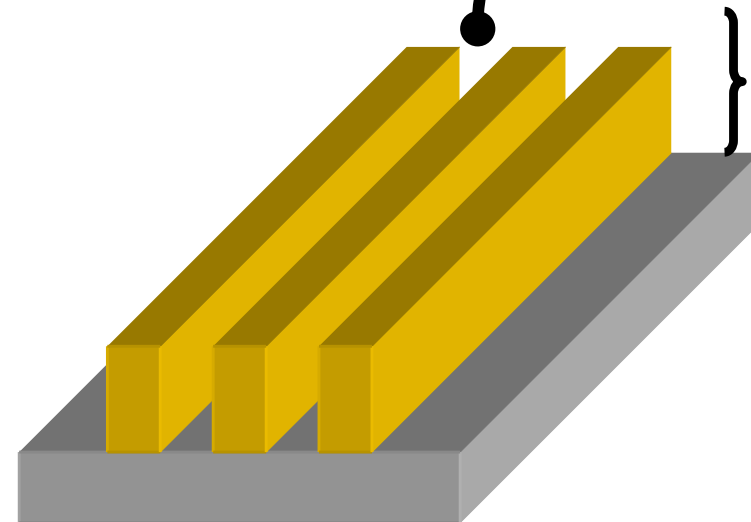
- Higher-aspect-ratio (smaller space) resist pattern

Interlayer dielectric resin

- Thicker than metal layers
- High sensitivity, high resolution

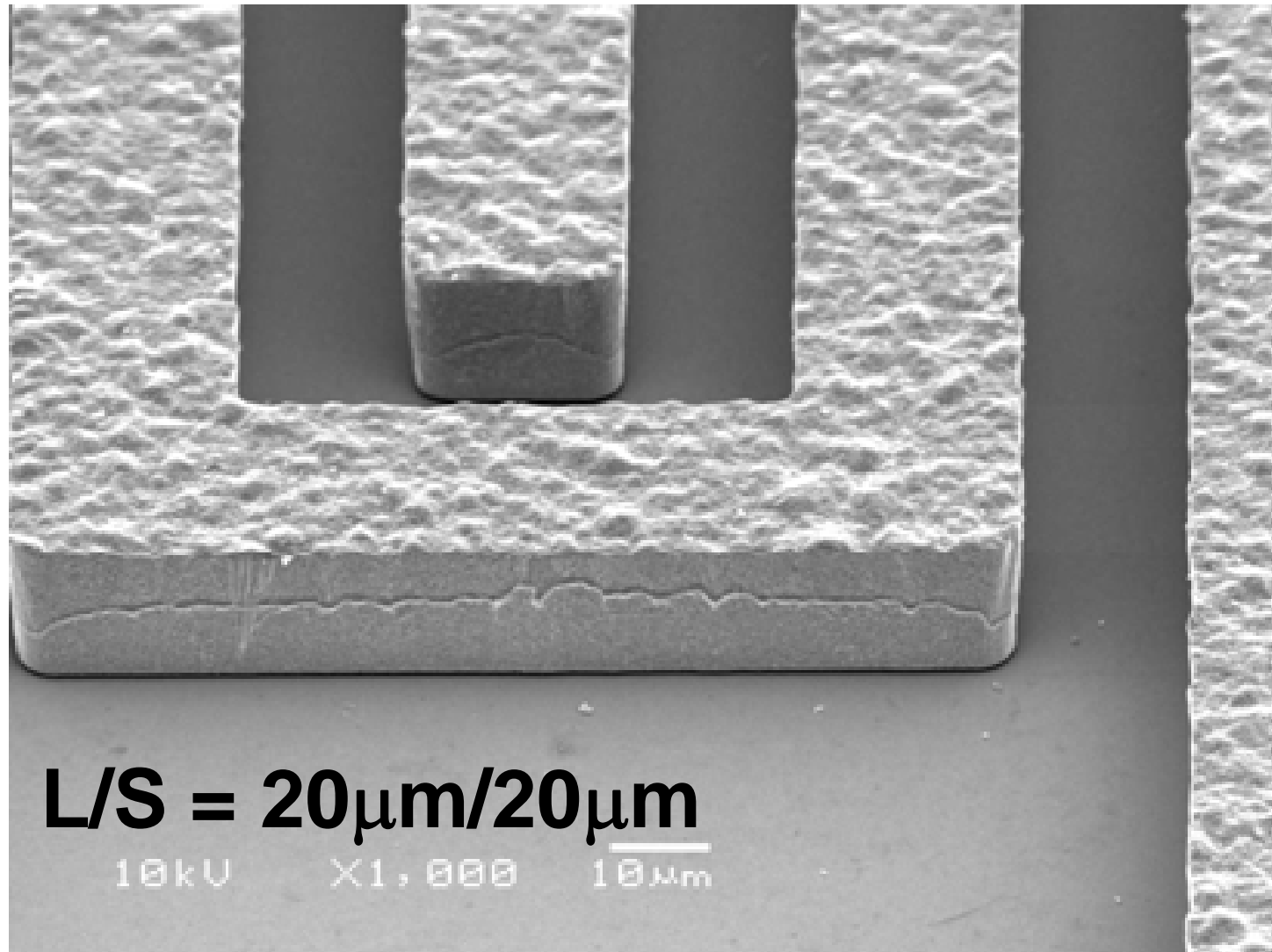


Conventional Cu wiring
1 ~ 5 μm thick



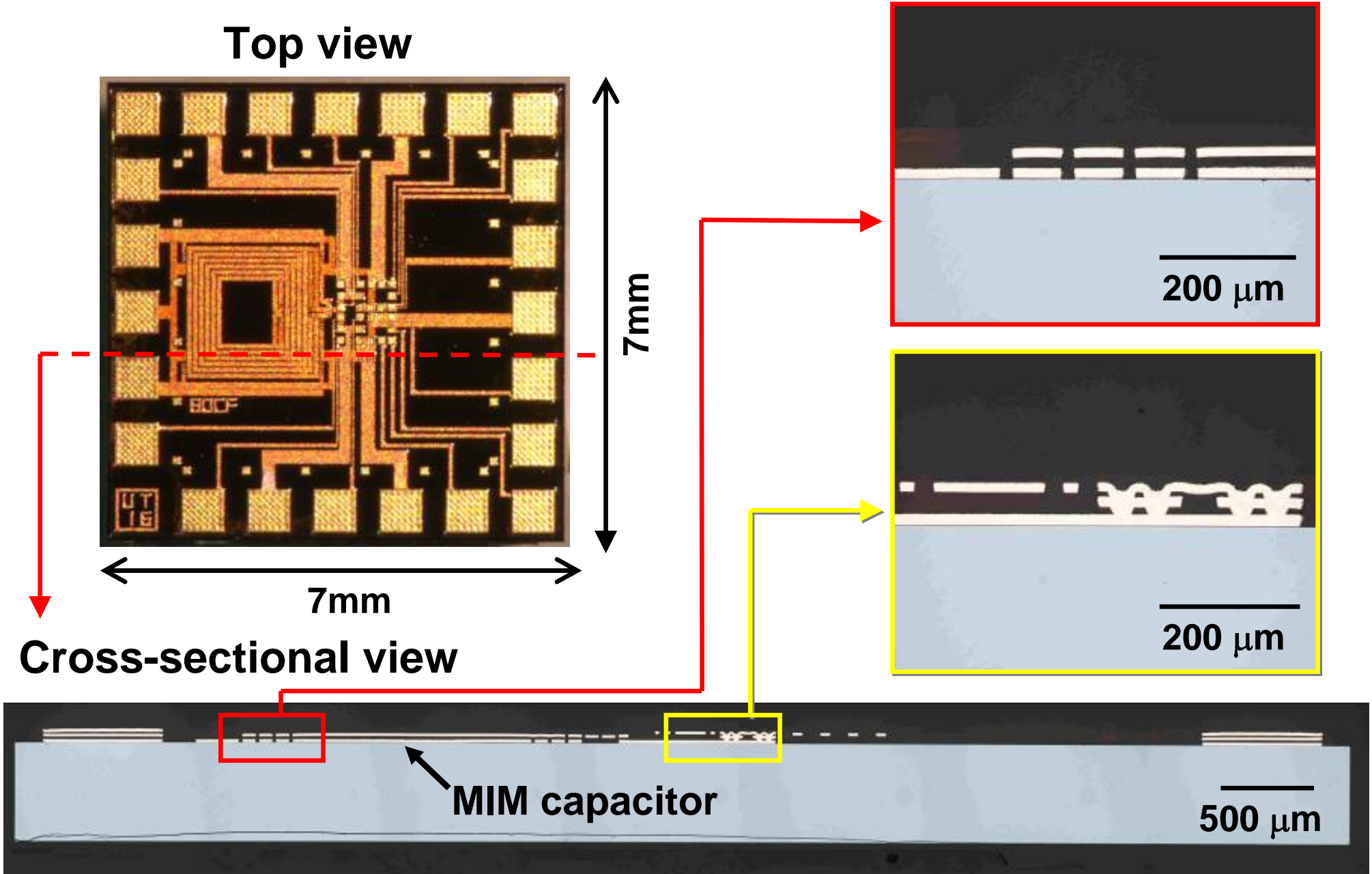
This work
15 μm thick

Fabricated 15- μm -Thick Cu Wiring

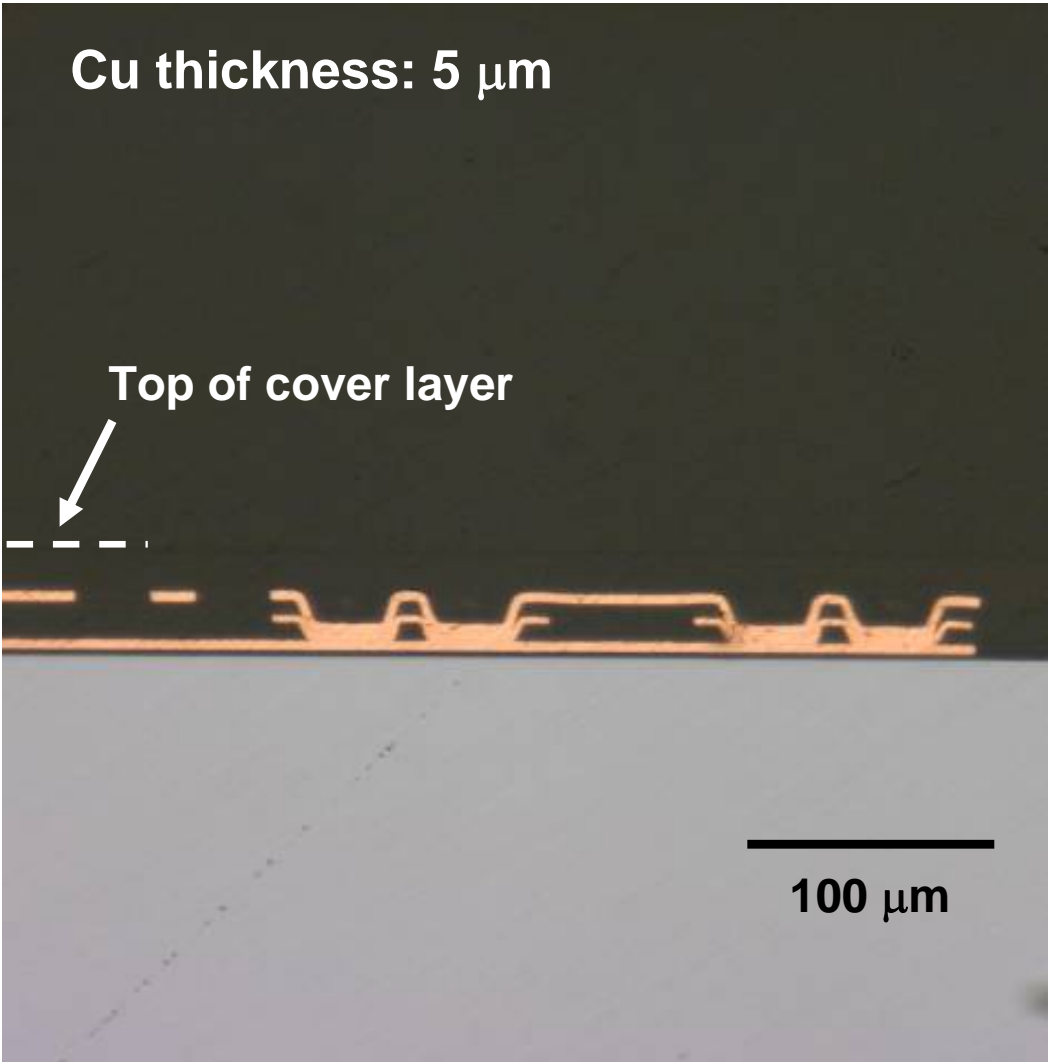
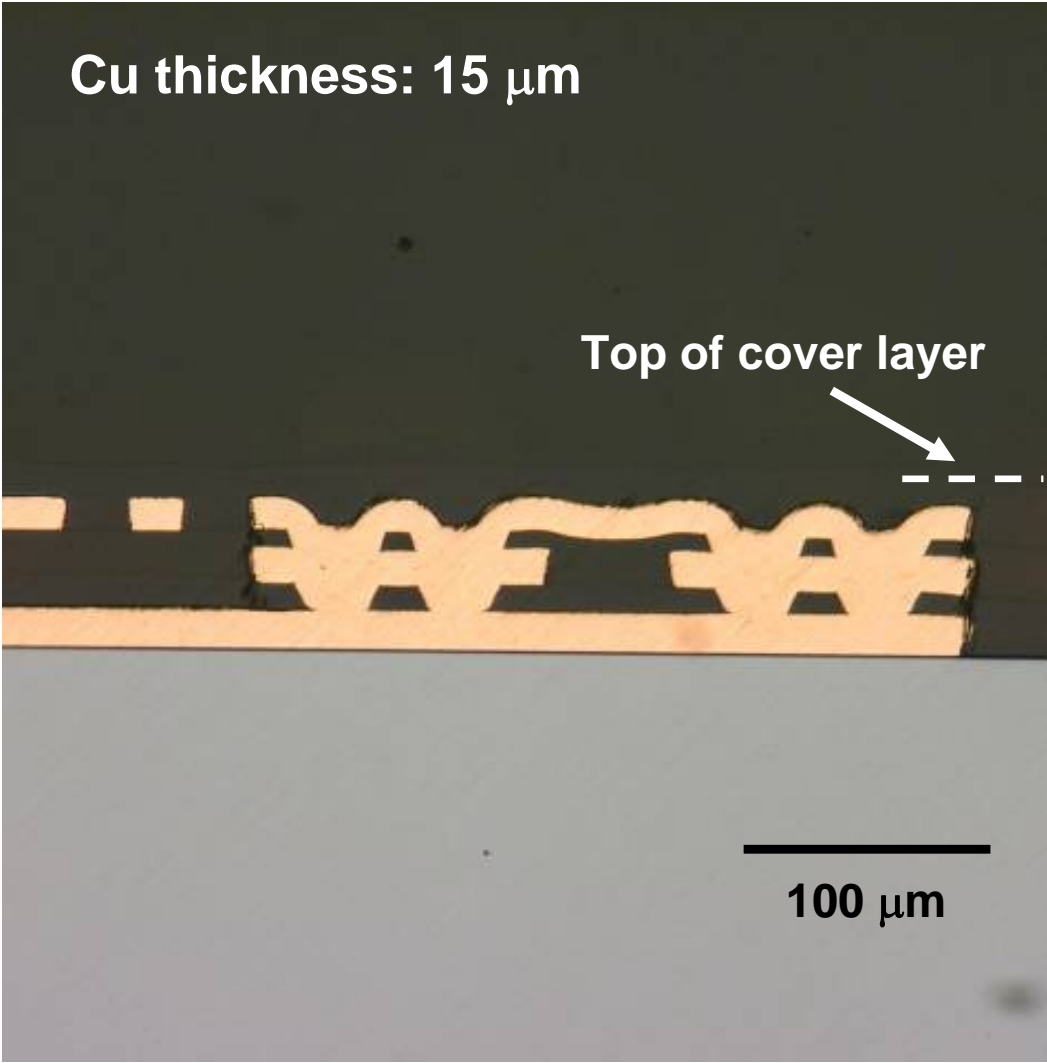


15 μm thick, Line/Space = 20 μm /20 μm

Photographs of Fabricated Si Interposer (1)

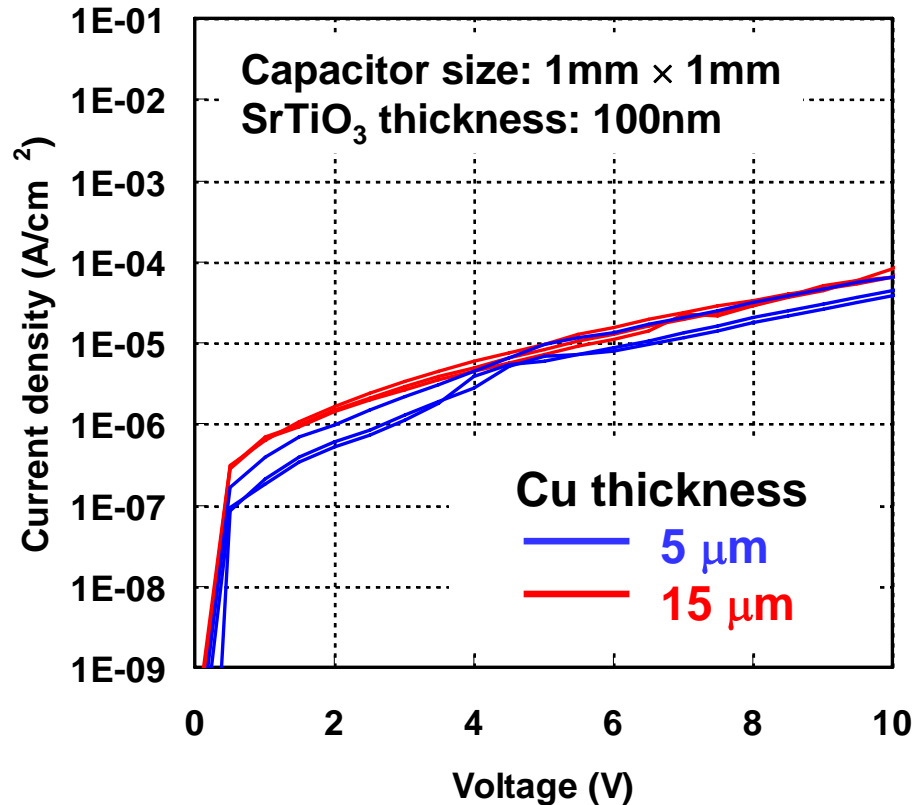


Photographs of Fabricated Si Interposer (2)

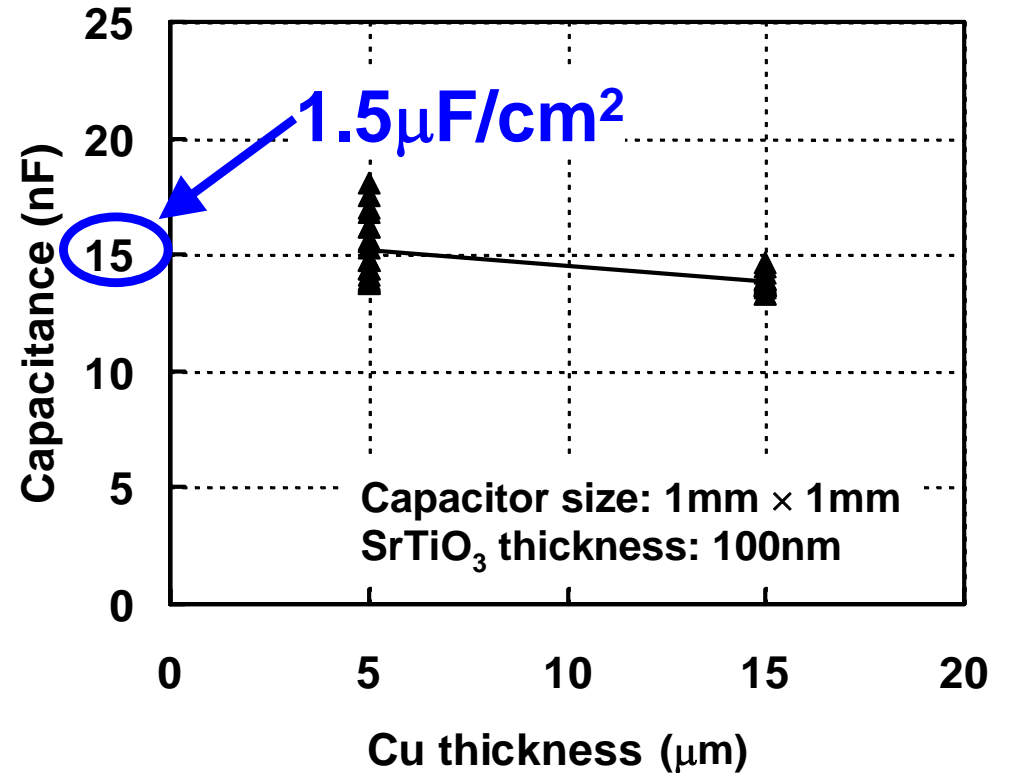


Properties for Embedded SrTiO₃ Capacitors

Leakage current



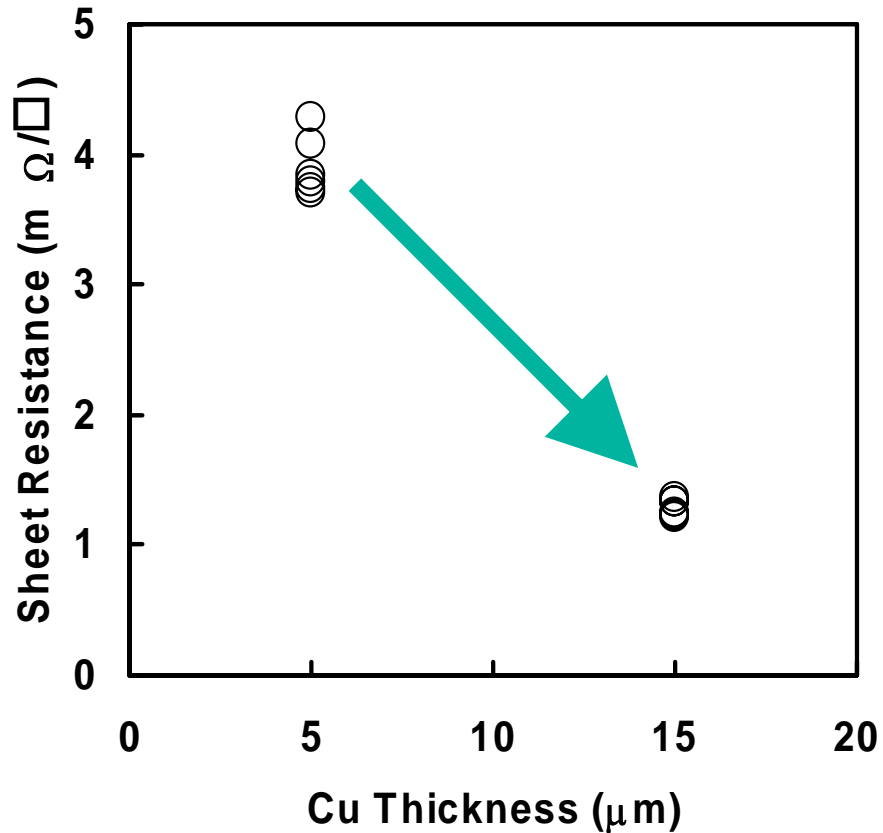
Capacitance



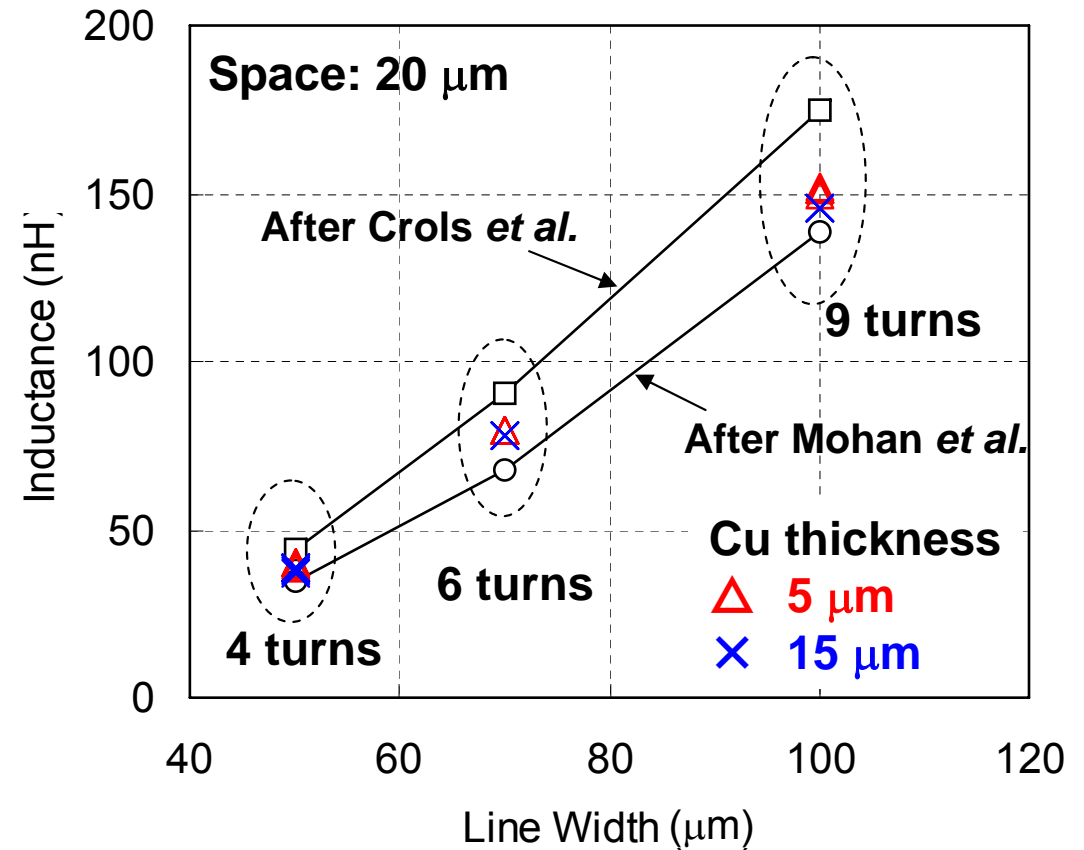
Capacitor properties are not affected by Cu thickness.

Properties of Cu Wirings and Spiral Inductors

Sheet resistance



Inductance



According to Cu thickness, only sheet resistance reduces.

Outline

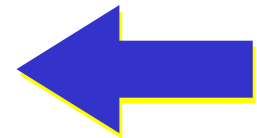
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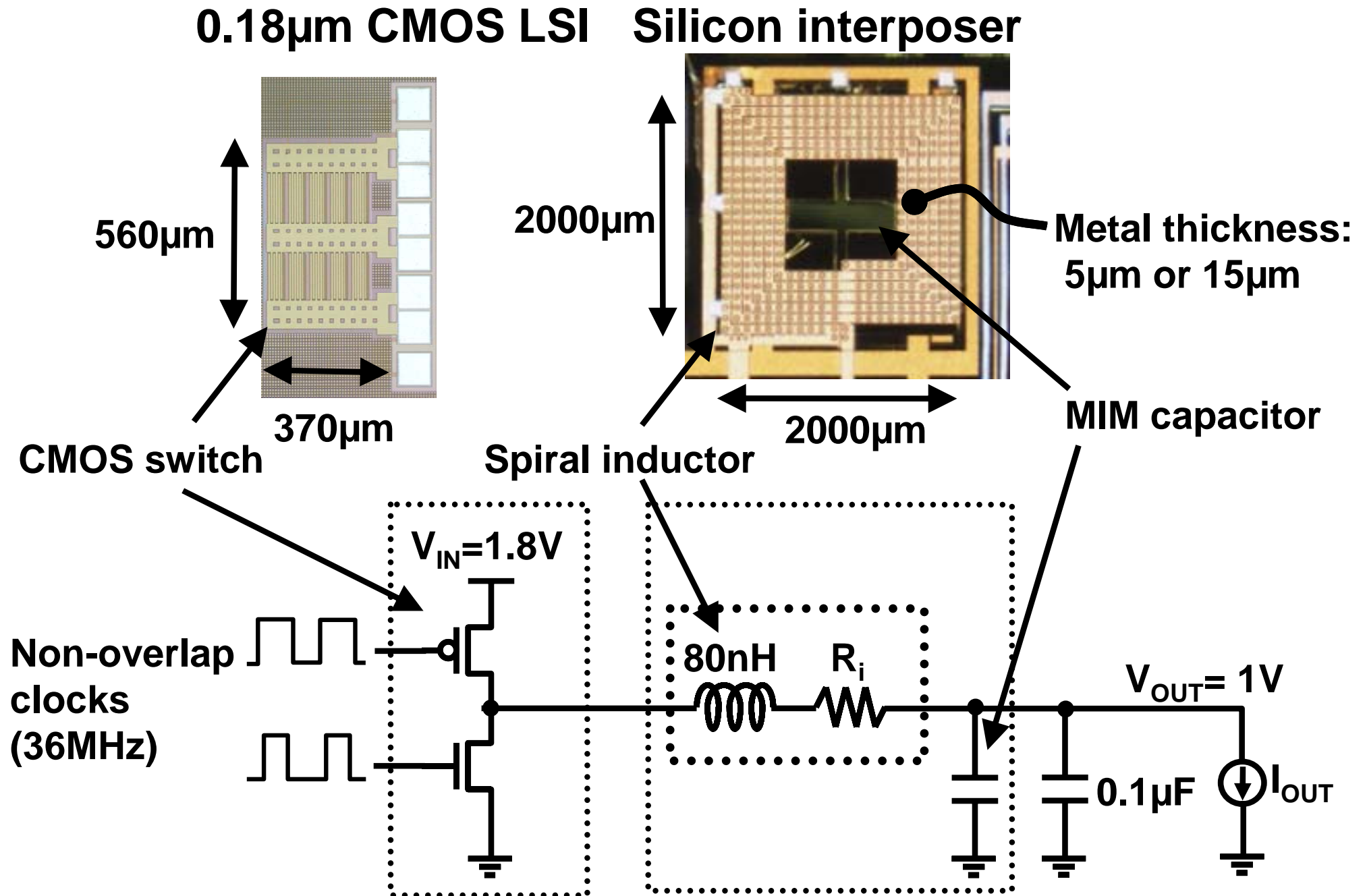
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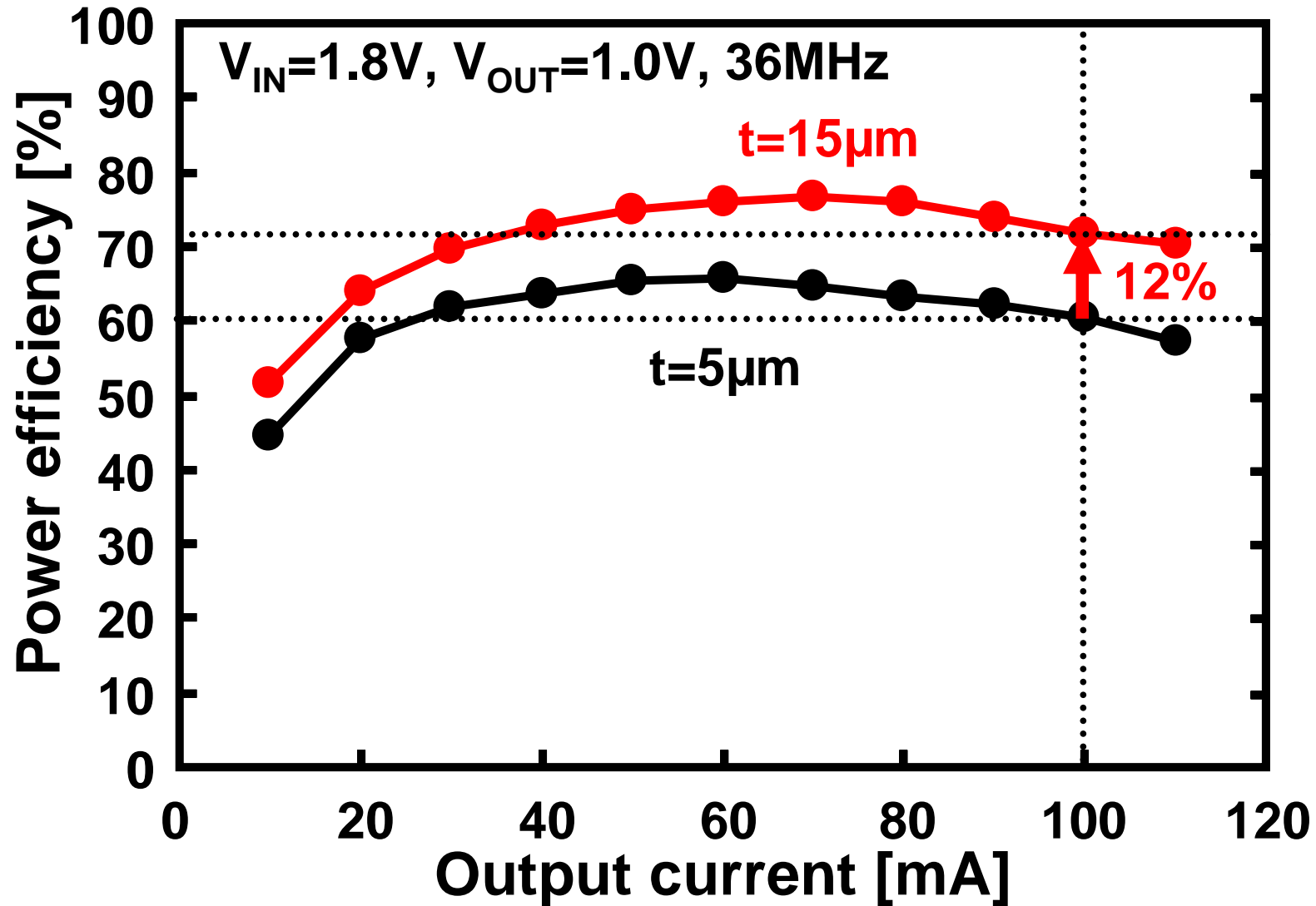


Summary

Fabricated Buck Converter



Measured Efficiency of Buck Converter



A 15- μm -thick inductor improves power efficiency by 12 %.

Summary

3D stacked buck converter with C and L on Si Interposer

1.5 μ F/cm² SrTiO₃ (STO) capacitor

- 100nm
- $\epsilon_r > 100$

15 μ m thick inductor

- 2mm x 2mm
- 80nH

Si interposer with a 15- μ m-thick inductor improves power efficiency of the buck converter by 12 %.

Acknowledgement

This work was entrusted by NEDO “Development of Functionally Innovative 3D-Integrated Circuit (Dream Chip) Technology” project that is based on the Japanese government's METI “IT Innovation Program”.